

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	19329	((438/149) or (438/151) or (438/154) or (438/161) or (438/169) or (438/174) or (438/180) or (438/181) or (438/184) or (438/185) or (438/197) or (438/199) or (438/211) or (438/213) or (438/214) or (438/216) or (438/217) or (438/218) or (438/221) or (438/229) or (438/230) or (438/231) or (438/232) or (438/279) or (438/289) or (438/294) or (438/296) or (438/299) or (438/300) or (438/301) or (438/302) or (438/311) or (257/288) or (257/347) or (257/330) or (257/333) or (257/332) or (257/240) or (257/241) or (257/243) or (257/344)).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/12/07 20:47
L2	20	1 and (decade near10 concentration)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/07 21:42
L3	5	1 and ((decade near10 concentration) near10 extension\$1)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/07 20:55
L4	6	((decade near10 concentration) near10 extension\$1)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/07 20:58
L5	1	4 not 3	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/07 20:55
L6	9	((decade near10 concentration) near10 abrupt\$3)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/07 20:58

L7	1124	(438/514).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/12/07 21:07
L8	2	7 and (decade near10 concentration)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/07 21:07
L9	1291	(438/151).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/12/07 21:39
L10	1	9 and (decade near10 concentration)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/07 21:40
L11	255	(438/153).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/12/07 21:41
L12	0	11 and (decade near10 concentration)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/07 21:42
S1	0	("10713971").PN.	USPAT	OR	OFF	2005/02/01 12:28
S2	1	("6677646").PN.	USPAT	OR	OFF	2005/01/05 19:32
S3	10	((("6429055") or ("6403433") or ("6225229") or ("6225173") or ("6187620") or ("6184097") or ("6010921") or ("5472897") or ("5468665") or ("5300447")).PN.	USPAT	OR	OFF	2005/01/05 19:34
S4	2	("0139273").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/01/05 19:35

S5	0	("Wo139273").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/01/05 19:50
S6	16887	((438/149) or (438/151) or (438/154) or (438/161) or (438/169) or (438/174) or (438/180) or (438/181) or (438/184) or (438/185) or (438/197) or (438/199) or (438/211) or (438/213) or (438/214) or (438/216) or (438/217) or (438/218) or (438/221) or (438/229) or (438/230) or (438/231) or (438/232) or (438/279) or (438/289) or (438/294) or (438/296) or (438/299) or (438/300) or (438/301) or (438/302) or (438/311) or (257/288) or (257/347) or (257/330) or (257/333) or (257/332) or (257/240) or (257/241) or (257/243) or (257/344)).CCLS	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/12/07 20:37
S7	3043	S6 and (soi or (silicon adj on adj insulator))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/01/05 20:17
S8	221	S7 and ((recess\$3 or trench\$3 or groov\$3) near5 (channel or (channel near2 region)))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/01/05 20:19
S9	645	S7 and ((recess\$3 or trench\$3 or groov\$3 or thin\$4) near5 (channel or (channel near2 region)))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/01/05 20:19
S10	301	S9 and (spacer\$1)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/01/05 20:22

S11	658	(LOCOS or (local adj oxidation adj of adj silicon)) same (remov\$3 or etch\$3) same vapor	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/01 12:37
S12	51	S11 same recess\$3	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/01 12:35
S13	0	(LOCOS or (local adj oxidation adj of adj silicon)) near3 (remov\$3 or etch\$3) near vapor	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/01 12:38
S14	0	(LOCOS or (local adj oxidation adj of adj silicon)) near5 (remov\$3 or etch\$3) near vapor	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/01 13:18
S15	1134	(LOCOS or (local adj oxidation adj of adj silicon)) near5 (remov\$3 or etch\$3)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/01 13:50
S16	553	S15 and (trench\$2 or groov\$2)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/01 13:23
S17	2	(LOCOS or (local adj oxidation adj of adj silicon)) near5 (remov\$3 or etch\$3) same (vapor near2 etch\$3)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/01 13:52
S18	0	(LOCOS or (local adj oxidation adj of adj silicon)) near5 (vapor near2 etch\$3)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/01 13:53

S19	385	(vapor near2 etch\$3) near3 ("HF" or hydrofluoric)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/01 14:10
S20	165	S19 and (silicon adj dioxide)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/01 13:56
S21	84	(vapor near2 etch\$3) near3 ("HF" or hydrofluoric) and (NH3 or ammonia)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/01 14:14
S22	34	S21 and ((thermal near oxid\$4) or (silicon adj dixoide) or sio2)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/01 14:13
S23	7	(vapor near2 etch\$3) near3 ("HF" or hydrofluoric) same (NH3 or ammonia)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/01 14:14